



Dr. Wontae Noh

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Wontae Noh is the Distinguished R&D Expert of Wonik IPS and works on providing the chemistry solutions for both vapor depositions and dry etching processes. His expertise focuses on the development of new precursors and inhibitor molecules for ALD technology. His contribution includes developing novel liquid precursors for ALD such as those used for metal oxides and nitrides as well as Si based thin films. He has co-authored multiple scientific papers and is listed as an inventor on several patents.

Prior to joining Wonik IPS, he was the R&D Group manager and the key project manager of Air Liquide. He also worked as a Postdoctoral Fellow in Harvard University after earning his Ph.D. degree from University of Illinois at Urbana-Champaign. Outside of work, he spends most time playing with two daughters.